

Miika Mattinen

List of Publications by Citations

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35
papers

573
citations

16
h-index

23
g-index

36
ext. papers

711
ext. citations

5.6
avg, IF

4.03
L-index

#	Paper	IF	Citations
35	Atomic Layer Deposition of Crystalline MoS ₂ Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700123	4.6	75
34	Atomic Layer Deposition of Rhenium Disulfide. <i>Advanced Materials</i> , 2018 , 30, e1703622	24	45
33	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS ₂ and ZrS ₂ , for Optoelectronics. <i>Chemistry of Materials</i> , 2019 , 31, 5713-5724	9.6	36
32	Review Article: Atomic layer deposition of optoelectronic materials. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019 , 37, 030801	1.3	34
31	Atomic Layer Deposition of PbI ₂ Thin Films. <i>Chemistry of Materials</i> , 2019 , 31, 1101-1109	9.6	34
30	Low-Temperature Wafer-Scale Deposition of Continuous 2D SnS Films. <i>Small</i> , 2018 , 14, e1800547	11	33
29	Scalable Route to the Fabrication of CH ₃ NH ₃ PbI ₃ Perovskite Thin Films by Electrodeposition and Vapor Conversion. <i>ACS Omega</i> , 2016 , 1, 1296-1306	3.9	32
28	Nucleation and Conformality of Iridium and Iridium Oxide Thin Films Grown by Atomic Layer Deposition. <i>Langmuir</i> , 2016 , 32, 10559-10569	4	24
27	Atomic layer deposition and characterization of Bi ₂ Te ₃ thin films. <i>Journal of Physical Chemistry A</i> , 2015 , 119, 2298-306	2.8	23
26	Atomic Layer Deposition of Iridium Thin Films Using Sequential Oxygen and Hydrogen Pulses. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 15235-15243	3.8	23
25	Atomic layer deposition of crystalline molybdenum oxide thin films and phase control by post-deposition annealing. <i>Materials Today Chemistry</i> , 2018 , 9, 17-27	6.2	22
24	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. <i>Chemistry of Materials</i> , 2018 , 30, 3499-3507 ²¹	9.6	21
23	Atomic Layer Deposition of Photoconductive CuO Thin Films. <i>ACS Omega</i> , 2019 , 4, 11205-11214	3.9	19
22	Low-temperature atomic layer deposition of copper(II) oxide thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 01A109	2.9	18
21	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie - International Edition</i> , 2018 , 57, 14538-14542	16.4	16
20	Atomic Layer Deposition of Molybdenum and Tungsten Oxide Thin Films Using Heteroleptic Imido-Amidinato Precursors: Process Development, Film Characterization, and Gas Sensing Properties. <i>Chemistry of Materials</i> , 2018 , 30, 8690-8701	9.6	16
19	Van der Waals epitaxy of continuous thin films of 2D materials using atomic layer deposition in low temperature and low vacuum conditions. <i>2D Materials</i> , 2020 , 7, 011003	5.9	13

18	Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 041506	2.9	12
17	Atomic Layer Deposition of 2D Metal Dichalcogenides for Electronics, Catalysis, Energy Storage, and Beyond. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2001677	4.6	12
16	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020921	2.9	10
15	Atomic Layer Deposition of Intermetallic Co ₃ Sn ₂ and Ni ₃ Sn ₂ Thin Films. <i>Advanced Materials Interfaces</i> , 2019 , 6, 1801291	4.6	8
14	Atomic layer deposition of lanthanum oxide with heteroleptic cyclopentadienyl-amidinate lanthanum precursor - Effect of the oxygen source on the film growth and properties. <i>Thin Solid Films</i> , 2018 , 660, 199-206	2.2	7
13	Atomic Layer Deposition of PbS Thin Films at Low Temperatures. <i>Chemistry of Materials</i> , 2020 , 32, 8216-8228	4.3	7
12	Studies on solid state reactions of atomic layer deposited thin films of lithium carbonate with hafnia and zirconia. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020929	2.9	5
11	Selective etching of focused gallium ion beam implanted regions from silicon as a nanofabrication method. <i>Nanotechnology</i> , 2015 , 26, 265304	3.4	5
10	Nickel Germanide Thin Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2019 , 31, 5314-5319	9.6	5
9	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl ₂ (TMPDA) and Tert-Butylhydrazine as Precursors. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2019 , 216, 1900058	1.6	4
8	Controlling Atomic Layer Deposition of 2D Semiconductor SnS ₂ by the Choice of Substrate. <i>Advanced Materials Interfaces</i> , 2020 , 7, 2001046	4.6	4
7	Toward epitaxial ternary oxide multilayer device stacks by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020602	2.9	3
6	Rhenium Metal and Rhenium Nitride Thin Films Grown by Atomic Layer Deposition. <i>Angewandte Chemie</i> , 2018 , 130, 14746-14750	3.6	2
5	Atomic Layer Deposition of Zinc Glutarate Thin Films. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700512	4.6	2
4	Atomic layer deposition of TbF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2021 , 39, 022404	2.9	2
3	Atomic Layer Deposition of Insulating AlF ₃ /Polyimide Nanolaminate Films. <i>Coatings</i> , 2021 , 11, 355	2.9	1
2	Atomic layer deposition of GdF ₃ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022 , 40, 022402	2.9	0
1	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. <i>Dalton Transactions</i> , 2021 , 50, 13264-13275	4.3	

